

Index

- 0th order, 22
- 0th order Bessel-like beam, 161
- 1D amplitude grating, 25
- 1D gratings, 147
- 2D binary phase grating, 32
- 2D phase grating, 33
- 4-level and 8-level axicons, 198
- 4-level and 8-level circular gratings, 196
- 4-level FZP, 53
- 4-level phase grating, 47
- 4-level SPP, 206
- 8-level 1D phase grating, 48
- 8-level axicon, 50

A

- aberration-corrected FZP, 105
- aberration correction techniques, 90
- aberration introduced by glass substrate, 96
- aberrations, 90
- accelerating Airy beams, 160, 204
- accelerating beams, 160
- achromatization, 9
- amplitude FZP, 133
- amplitude grating, 6
- amplitude-only DOEs, 122
- analog method, 137
- aperture function, 17
- array of ring patterns, 141
- astigmatism, 188
- autocorrelation function, 166
- axicon, 131

- axilens, 58, 81, 158
- azimuthal rotations, 54

B

- beam path steering element, 160
- beam shaping, 143
- Bessel beams, 199
- Bessel intensity profiles, 140
- Bessel-like beam, 76, 160
- binary 1D grating, 129
- binary axicon, 79
- binary spiral phase plate, 73
- blazed 1D grating, 206
- blazed 1D phase gratings, 49
- blazed axicons, 50
- blazed axilens, 59
- blazed FZP, 129
- blazed gratings, 5, 46
- blazed spiral phase plate, 133

C

- characterization of fabricated DOEs, 187
- charging problem, 188
- checkerboard grating, 34, 127, 131
- circle-by-circle fabrication, 181
- circular aperture, 79
- circular grating array, 204
- circular gratings, 37
- computer-generated Fourier amplitude hologram, 165
- computer-generated holographic optical elements, 143

computer reconstruction, 171
conical wavefront, 150
contamination pillar, 191
contamination spots, 191
continuous and discrete Fourier transforms, 27

D

diffraction, 1
diffraction-limited spot, 2
diffraction order, 23
diffraction pattern, 23, 29
diffractive axicons, 37
diffractive optical elements, 2, 17
diffractive optics, 1
discretized Fourier transform, 12
dispersive nature, 9
DOE on a fiber tip, 208
donut beam diameter, 54
donut beams, 156
donut intensity profile, 53
drift correction, 210
duty ratio error, 115

E

effective efficiency, 139
efficiency of light, 46
Eikonal equations, 62, 63
electron beam lithography, 175
elliptical FZPs, 40

F

fabrication recipes, 175
fabrication techniques, 175
far-field analysis, 24
far-field approximation, 78
far-field diffraction pattern, 126, 156, 203
fill factor, 24
finite conjugate mode, 92
flower-shaped intensity profile, 157
focal depth, 58
focused ion beam, 175

focused ion beam lithography, 205
focused ion beam milling, 208
focused ring pattern, 140, 172
for and *if* loops, 25
forked gratings, 147
Fourier analysis, 20
Fourier coefficients, 21
Fourier hologram, 165
Fourier transform, 12, 25
fractal zone plate, 187
fractional topological charges, 55
Fraunhofer approximation, 11, 78
Fraunhofer diffraction
 formula, 166
Fresnel approximation, 78
Fresnel diffraction integral, 24, 76
Fresnel diffraction, 79
Fresnel holograms, 169
Fresnel lens, 4
Fresnel regime, 76
Fresnel zone plate, 17, 175
fringe patterns, 148

G

Gerchberg–Saxton algorithm, 60
gradient ring lens, 73
grating, 3
grating convention, 7
grating equation, 20
grating shape, 5
grayscale DOEs, 44
grayscale FZP, 51
grayscale SPP, 55

H

helical axicon, 141, 156
helical wave, 156
helical wavefronts, 53
higher-order Bessel beams, 156
Huygens–Fresnel theory, 10
Huygens' principle, 2
hybrid DOEs, 17, 122
hybrid optical elements, 119

I

infinite conjugate mode, 92
interferograms, 143
inverse Fourier transform
 algorithm, 60
iterative Fourier transform
 algorithm, 44

L

Laguerre–Gaussian beam, 157
line focus, 39
lithography file design, 175
low- and high-pass filtering, 167

M

MATLAB®, 2, 17, 48, 76, 94, 127,
 148, 178
maximum efficiency, 31
mesh generation technique, 63
mesh nodes, 63, 68, 70
metallization, 188
micro-optical element
 fabrication, 175
modulo- 2π phase addition
 technique, 122
multifunctional DOEs, 119, 134,
 152, 203
multilevel DOEs, 46
multilevel FZP, 52
multilevel SPP, 55, 57, 206
multilevel structure fabrication, 196
multiple-beam interference, 163
multiplexed diffractive
 optics, 119

N

negative axicon, 138

O

off-axis axicon, 154
off-axis axilens, 158
off-axis Bessel beams, 154
optical microscope, 187

P

paraxial approximation, 76
phase grating, 29
phase multiplexing, 119
phase-only DOEs, 122
photolithography, 175
photon sieve, 187
pixel size, 27
plasma etching, 186
polygon approximation, 181
polygonal path scanning, 181
prism, 8

Q

Quanta 3D FEG (FEI), 178
Quanta™ 400F (FEI), 178
quasi-achromatic, 135

R

RAITH150^{TWO}, 178
raster scanning, 182
ray tracing, 94
reflective–diffractive
 combinations, 119
refractive–diffractive
 combinations, 119
resist thickness error, 115
resist-thickness-versus-dose
 characterization, 197
ring pattern, 128

S

sampling criteria, 27
sampling periods, 78
scalar diffraction, 24
scalar theory, 2
scanning electron microscope, 191
self-image, 85
serpentine scanning, 183
sinusoidal axicon, 152
sinusoidal grating, 31, 149
Snell's law, 3, 96
spatial frequencies, 24

spherical aberration, 90
spherical wavefront, 149
spiral phase plates, 53
stack method, 206
stigmatism correction, 191
stitching error, 192
substrate aberration, 108
surface profiler, 187

T

tailored focal depth, 158
Talbot carpet, 85
Talbot effect, 84
Talbot planes, 85
tilted-plane wavefront, 148
tilted ring pattern, 154

topological charge, 53, 156
transition between refraction and
diffraction, 2
transition between refractive and
diffractive elements, 8
twin images, 62

V

vector method, 180

W

wet etching, 184

Z

zero padding, 28, 167–168



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